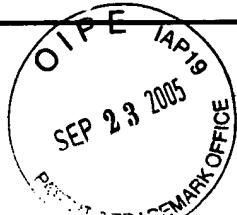


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**To Be Assigned**Invention: **CHEMICALLY AMPLIFIED POSITIVE PHOTOSENSITIVE RESIN COMPOSITION**I hereby certify that this **English Language abstract of JP 62-124556 - 2 Pages**  
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(71)Applicant : KONISHIROKU PHOTO IND  
CO LTD  
MITSUBISHI CHEM IND LTD

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(72)Inventor : NAKAI HIDEYUKI  
GOTO SEI  
SASA NOBUMASA  
TOMIYASU HIROSHI  
MAEDA YOSHIHIRO  
URANO TOSHIYOSHI

(54) PHOTOSENSITIVE COMPOSITION AND PHOTOSENSITIVE LITHOGRAPHIC  
PLATE MATERIAL

(57)Abstract:

PURPOSE: To obtain a photosensitive composition high in photosensitivity, wide in processing allowance at the time of development, and superior in resistance to processing chemicals by using a novolak type resin containing at least 3 different kinds of phenols only in combination with a positive type photosensitive material composed of a compound capable of generating acid on irradiation of actinic rays and an acid-decomposable type compound.

CONSTITUTION: The photosensitive resin composition contains the compound capable of generating acid on irradiation of actinic rays and a compound having at least one acid-decomposable bond, and the novolak type resin containing at least 3 different kinds of phenols. As the acid-decomposable compound, ones such as having an acetal or ketal group, or polymers each having a orthocarboxylic ester group on the principal chain, are used, preferably, in a amount of 5W70wt% of the total solid of the photosensitive resist-forming composition. As the novolak resin, polycondensed novolak resins containing at least 3 kinds of phenols are preferably used.

**LEGAL STATUS**

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